

Title (en)

Adjustment to desired value (trimming) on thin film resistors by ion sputtering.

Title (de)

Abgleich von Dünnschichtwiderständen durch Ionenzerstäubung.

Title (fr)

Ajustage de résistances en couche mince par pulvérisation à l'aide d'un faisceau d'ions.

Publication

**EP 0070809 A2 19830126 (EN)**

Application

**EP 82830171 A 19820615**

Priority

IT 4893281 A 19810720

Abstract (en)

A technique for adjusting to the desired value, thin film integrated resistors is made known. This method consists in exposing a resistor, whose thickness is greater than that necessary for the desired resistance, to ionic sputtering of the resistive material until a the resistor thickness is such as to correspond to the desired electric resistance. Ion-sputter etching is realised iether by means of a plasma or by means of an ion-gun.

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IPC 8 full level

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Cited by

EP1237164A1; GB2213986A; US6475400B2; US10680056B1; WO03052839A1

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